



Our Ref. No.: 051876.P538

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application for:

Min-Suk Lee, et al.

Serial No. 10/748,613

Filed: December 29, 2003

For: **METHOD FOR FABRICATING
SEMICONDUCTOR DEVICE WITH
FINE PATTERN**

Examiner: Vinh, Lan

Art Group: 1765

OK to enter

LV

3/24/06

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450
Box Amendment

RESPONSE TO OFFICE ACTION

Dear Commissioner:

In response to the outstanding Office Action mailed December 8, 2005, submitted herewith is a Terminal Disclaimer responsive to the provisional rejection of claims 1-12 on the grounds of non-statutory obviousness type double patenting over claims 19-24 of co-pending application 10/925,856 and of the provisional rejection of claims 13-25 on the grounds of non statutory obviousness type double patenting over claims 19-34 of co-pending application 10/925,856 in view of Chang.

Since the Terminal Disclaimer removes application no. 10/925,856 and since Chang was cited by the Examiner to provide the "step of loading the resulting semiconductor substrate structure into an etching equipment having at least two chamber/performing the etching step in-situ" as stated at page 3 of the Action, and does not provide the remaining elements taught by co-